

## PATENT ABSTRACTS OF JAPAN

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## (54) SUBSTRATE-PROCESSING DEVICE

## (57)Abstract:

PROBLEM TO BE SOLVED: To quickly and evenly dry the entire surface of a substrate.

SOLUTION: First and second diaphragms 2 and 3 of porous bodies, which prevent passage of a washing liquid while allowing the passage of fluid for drying are provided inside a process vessel 1 comprising a lid body which opens/ closes, with a first chamber 4 for supplying a liquid for drying, a second chamber 5 where a substrate 9 is housed, and a third chamber 6 for discharging the liquid for drying formed, and the first chamber 4 is connected to a drying- liquid supply pipe 7 with an interposed valve 7a, while the third chamber 6 is connected to a drying-liquid discharge part 8 with an interposed valve 8a.

